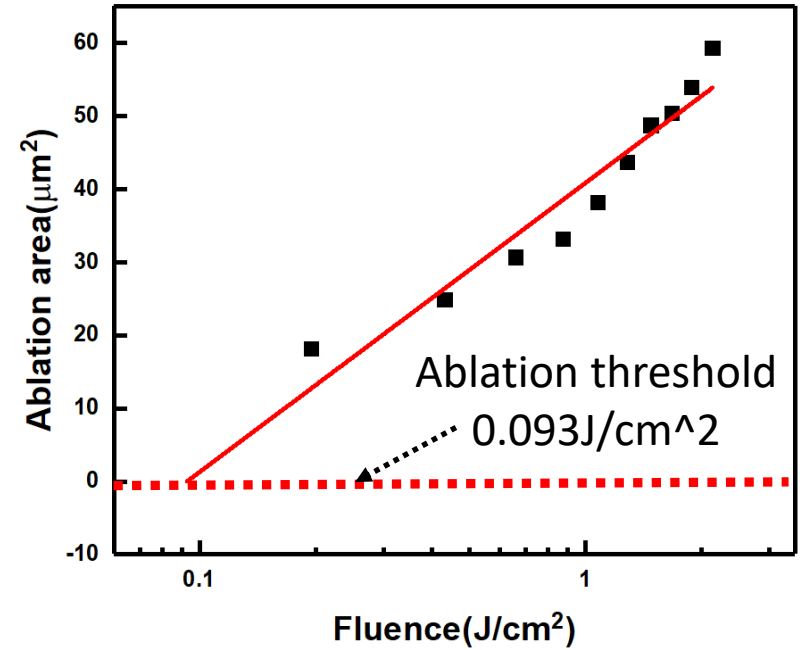
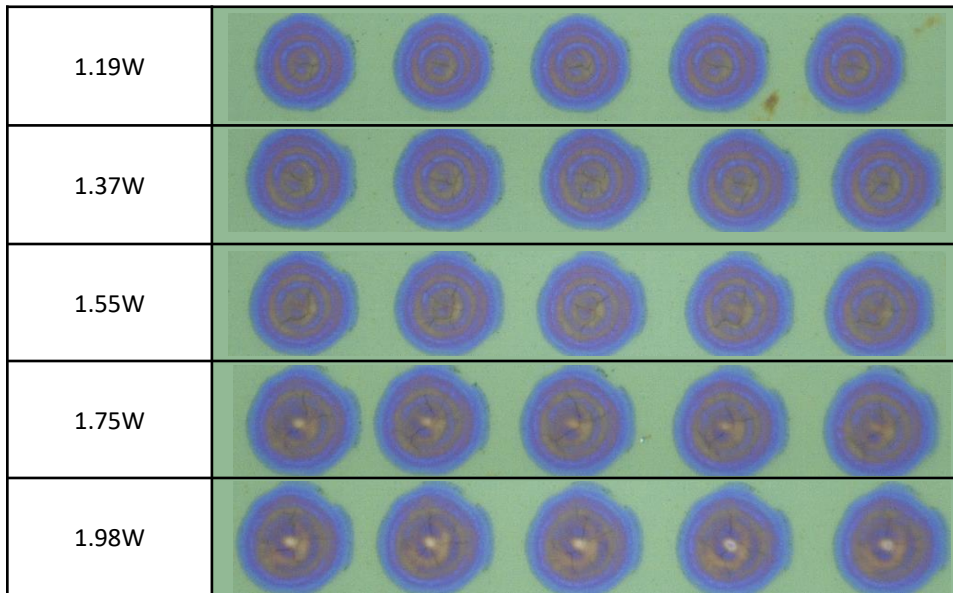
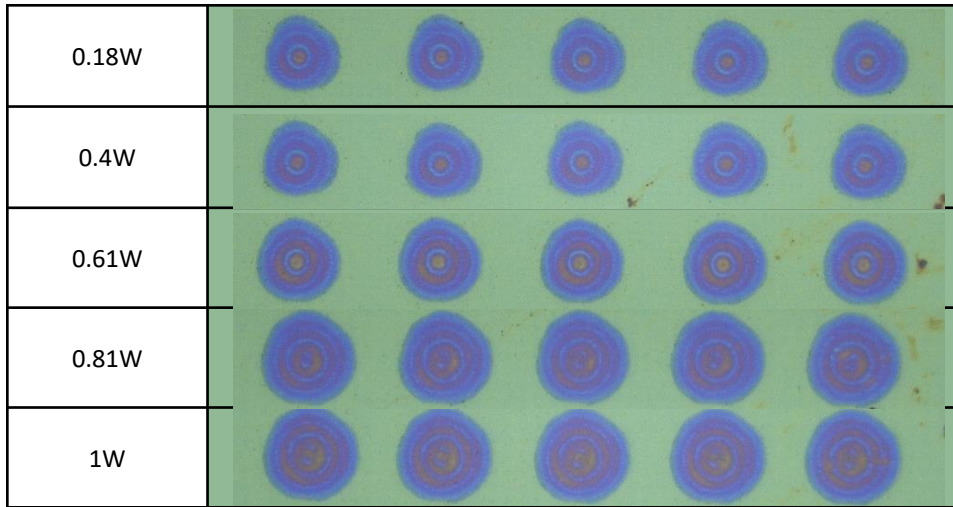


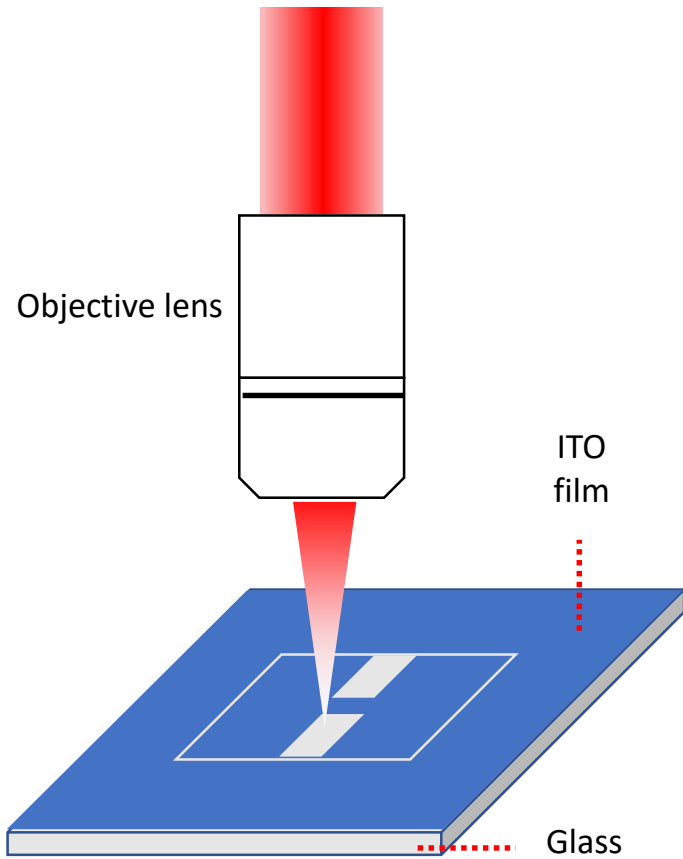
- ITO ablation threshold



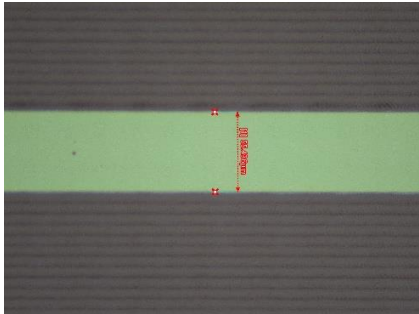
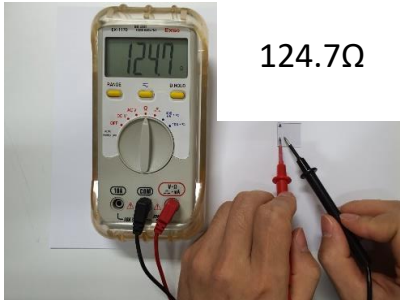
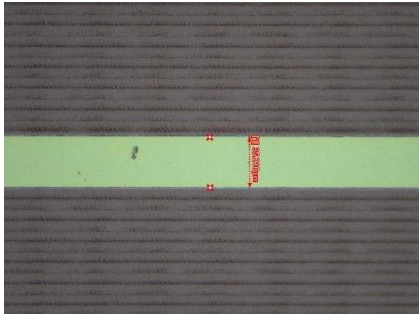
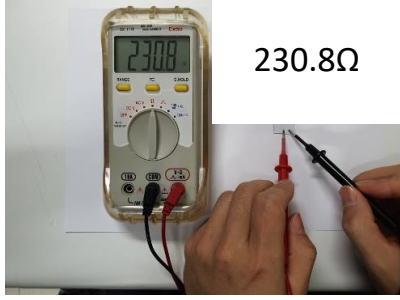
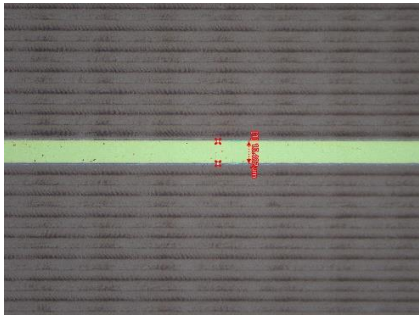

- Plan

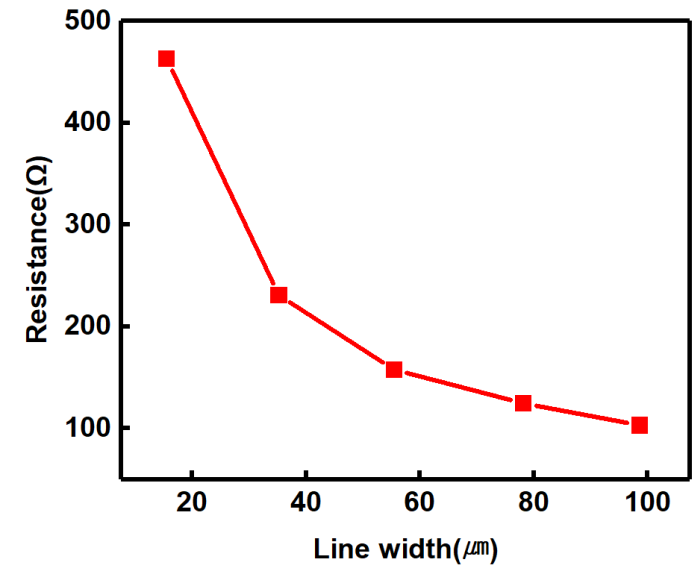
Ni, Cu, Ag, Al, Cr, Si₃N₄, Al₂O₃, SUS
 Ablation threshold 획득 및 비교분석

- Compact electrode fabrication

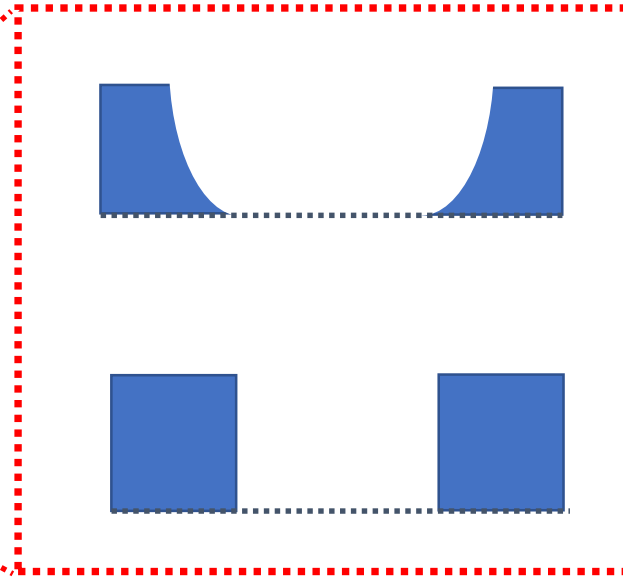
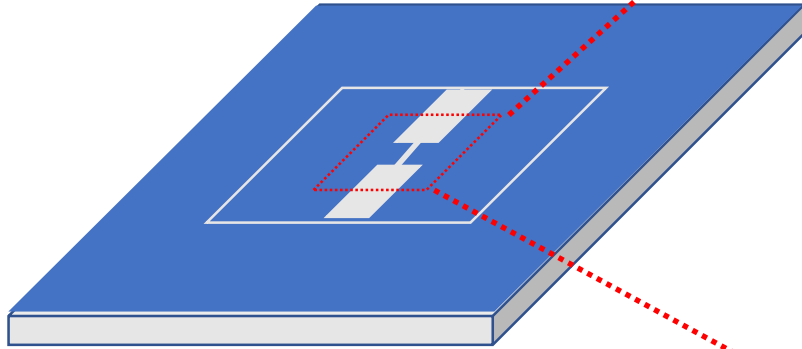


Line width	50배율	Resistance
No ablation		14.3Ω
100μm		103.2Ω
80μm		157.9Ω

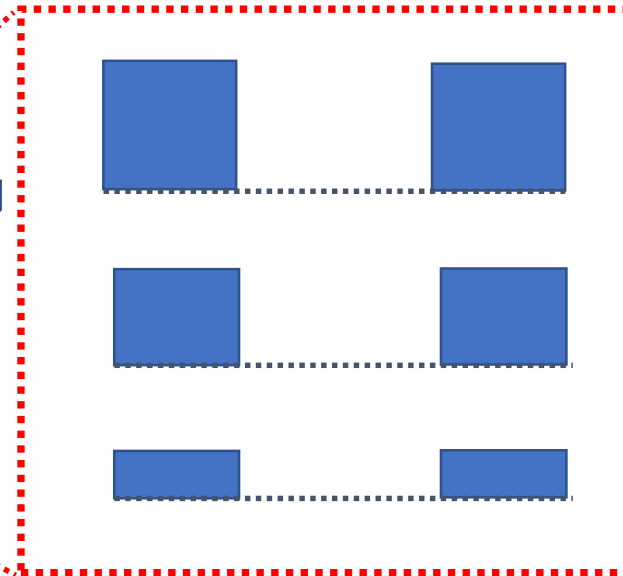
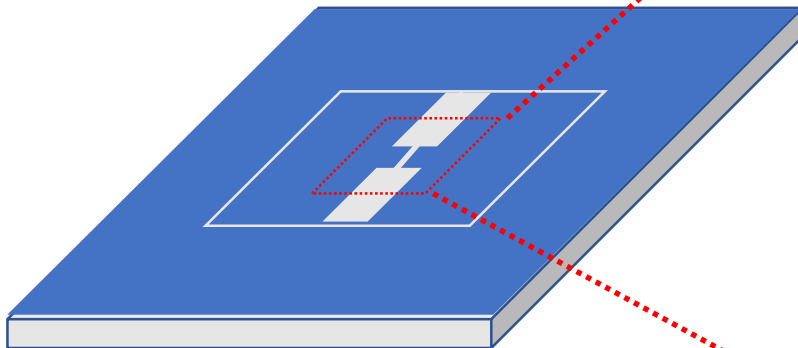
Line width	50배율	Resistance
60 μ m		 <p>124.7Ω</p>
40 μ m		 <p>230.8Ω</p>
20 μ m		 <p>463Ω</p>



- Plan 1

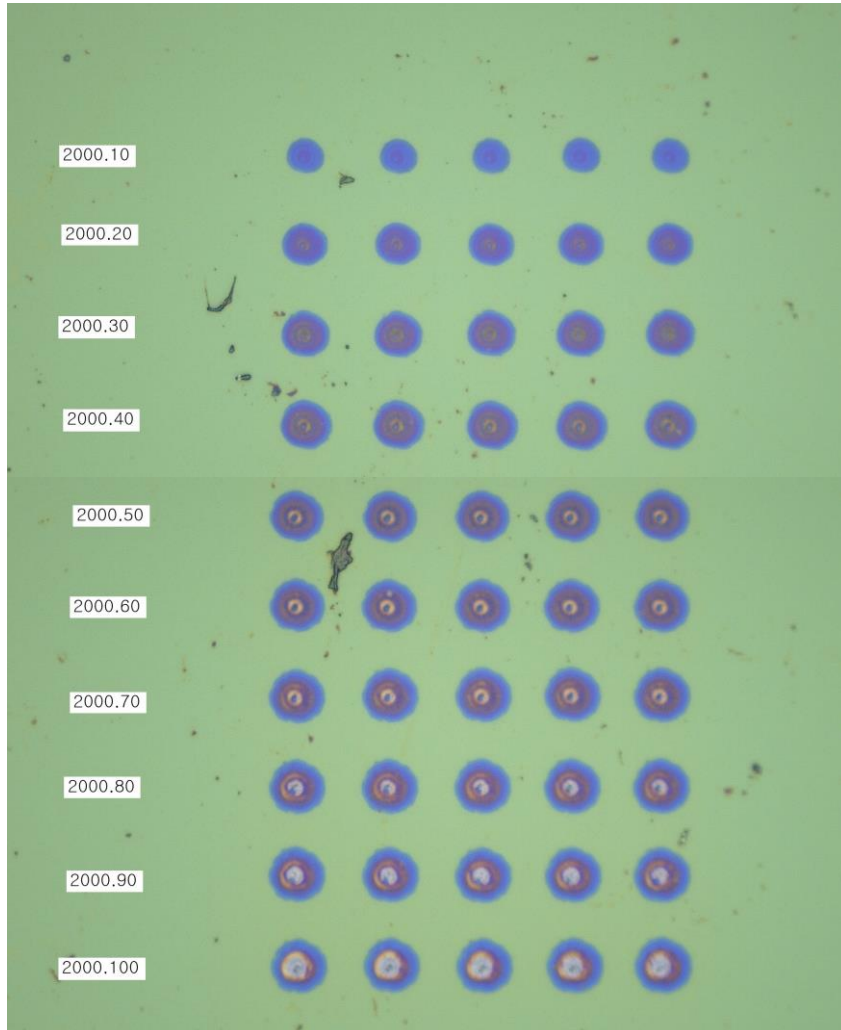


- Plan 2



- BDS ablation

- ITO



- Ni

